

**IN THE CLAIMS:**

Please cancel claims 1-7 without prejudice to the right to file such claims in a divisional application and without prejudice or disclaimer of the subject matter thereof.

Claims 1-7 (canceled)

8. (original) An apparatus for plasma processing which has a vacuum vessel forming a plasma producing part, a gas supplying means for supplying a gas to the vacuum vessel, an antenna generating an electric field in the plasma producing part, a Faraday shield provided at outer periphery of the vacuum vessel, a high-frequency electric source supplying a high-frequency electric power to the antenna and the Faraday shield, and an end point determination and detection means, said end point determination and detection means detecting the end point of cleaning of the inner wall of the vacuum vessel by detecting emission wavelength of reaction products.

9. (original) An apparatus for plasma processing which has a vacuum vessel forming a plasma producing part, a gas supplying means for supplying a gas to the vacuum vessel, an antenna generating an electric field in the plasma producing part, a Faraday shield provided at outer periphery of the vacuum vessel, a high-frequency electric source supplying a high-frequency electric power to the antenna and the Faraday shield, and an end point determination and detection means, said end point determination and detection means detecting the end point of cleaning of the inner wall of the vacuum vessel by detecting emission wavelength of a material of the vacuum vessel.